



CHARGE INDEPENDENT MODELING OF FLOATING GATE MOSFET

By

Ahmed Hossam Eldin Hamed Hassan

A Thesis Submitted to the Faculty of Engineering at Cairo University in Partial Fulfillment of the Requirements for the Degree of

MASTER OF SCIENCE

in

Electronics and Communications Engineering

FACULTY OF ENGINEERING, CAIRO UNIVERSITY GIZA, EGYPT 2018

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Under the Supervision of

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Title of Thesis:

Charge Independent Modeling of Floating Gate MOSFET

Key Words:

FGMOSFET; Devices Modeling; Parasitic Capacitances; Nano Electronics; Charge Trapping

Summary:

This Thesis studies the Floating- Gate MOSFET (FGMOSFET) for its importance in biomedical engineering and many modern low-power applications. A practical DC model for FGMOSFET is highly needed to be used in circuits simulators. A mathematical model for the parasitic capacitances of FGMOSFET in linear and saturation regions of operation is introduced. Then the resultant capacitance values in drain-current equation is applied. In parallel way, a simulation technique in literature for FGMOSFET is stated. Comparison between proposed model and simulation curves are done. The output curves and characteristic curves for FGMOSFET are drawn for various biases. The model proposed is a spice model for FGMOSFET and can be inserted in any circuit simulator such as Spector and various SPICE programs (i.e. HSPICE, WinSPICE, etc.). The model is verified by using 0.13um CMOS technology and Cadence Simulator based on BSIM3 models. The model is based on n-channel FGMOSFET. The model considers velocity saturation as short channel effect and bulk charge due to drain-to-source voltage as second order effect. The model is not a charge conservative. The maximum percentage of error in linear region is 9.6% and in saturation is 2.6%.



Disclaimer

I hereby declare that this thesis is my own original work and that no part of it has been submitted for a degree qualification at any other university or institute.

I further declare that I have appropriately acknowledged all sources used and have cited them in the references section.

Name: Ahmed Hossam Eldin Hamed Hassan Date:

Signature:

Dedication

To my beloved Parents,

Sisters,

Relatives

and

best Friends.

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Nomenclature

AC Alternative Current

BSIM Berkeley Short-Channel IGFET Model

CG Control Gate

CMOS Complementary Metal-Oxide-Semiconductor

CTF Charge-Trap flash

DC Direct Current

DeFET Differential electric field sensitive Field Effect

Transistor

DIBL Drain Induced Barrier Lowering

DSUB BSIM Parameter

EEPROM Electrically Erasable Programmable Read-

Only Memory

eFET electric field sensitive Field Effect Transistor

EKV Transistor Model Name

ETAO BSIM Parameter

FAMOS Field Applied Metal Oxide Semiconductor

FB Flat Band

FG Floating Gate

FGMOSFET Floating Gate Metal Oxide Semiconductor

Field Effect Transistor

FPGA Field Programable Gate Array

GAA Gate All Around

GB Gain Bandwidth

MOS Metal Oxide Semiconductor

MOSFET Metal Oxide Semiconductor Field Effect

Transistor

NAND Name of a logic gate

QFGMOSFET Quasi Floating Gate Metal Oxide

Semiconductor Field Effect Transistor

RAM Random Access Memory

SA Self-aligned

SONOS silicon-oxide-nitride-oxide-silicon

SOS silicon-on-sapphire

SPICE Simulation Program with

Integrated Circuit Emphasis

STI shallow trench isolator

TCAD Technology Computer Aided Design